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(54) **TARGET PROFILE FOR A PHYSICAL VAPOR DEPOSITION CHAMBER TARGET**
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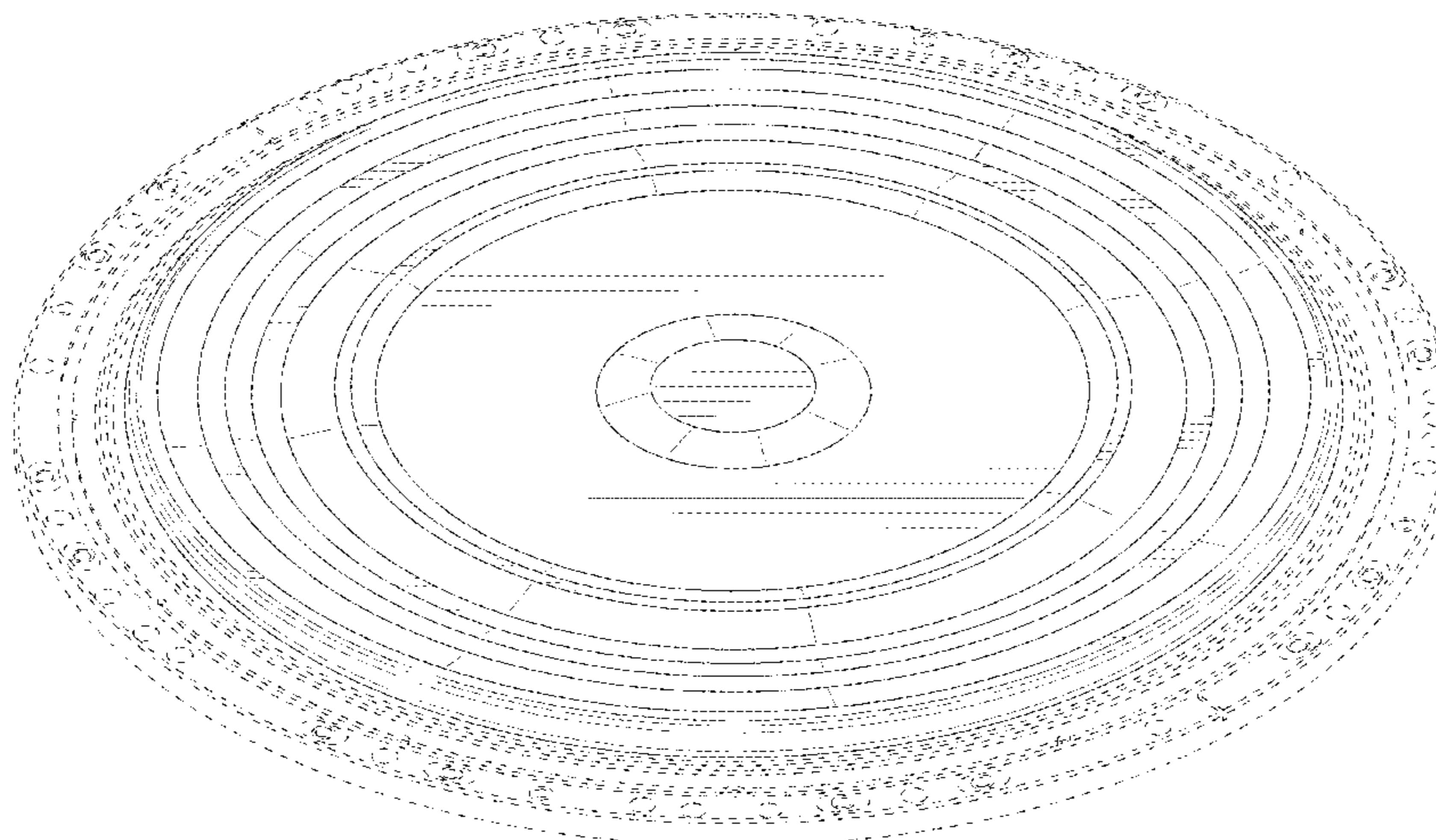
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See application file for complete search history.

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(57)

CLAIM

We claim the ornamental design for a target profile for a physical vapor deposition chamber target, as shown and described.

DESCRIPTION

FIG. 1 is a top perspective view of a target profile for a physical vapor deposition chamber target, according to the novel design.

FIG. 2 is a top plan view thereof.

FIG. 3 is a bottom plan view thereof.

FIG. 4 is a right side plan view thereof.

FIG. 5 is a left side plan view thereof.

FIG. 6 is a front view thereof.

FIG. 7 is a back view thereof; and,

FIG. 8 is an enlarged cross sectional view taken along line 8-8 in FIG. 2.

The dashed lines in the drawings represent unclaimed environment and form no part of the claimed design.

1 Claim, 6 Drawing Sheets

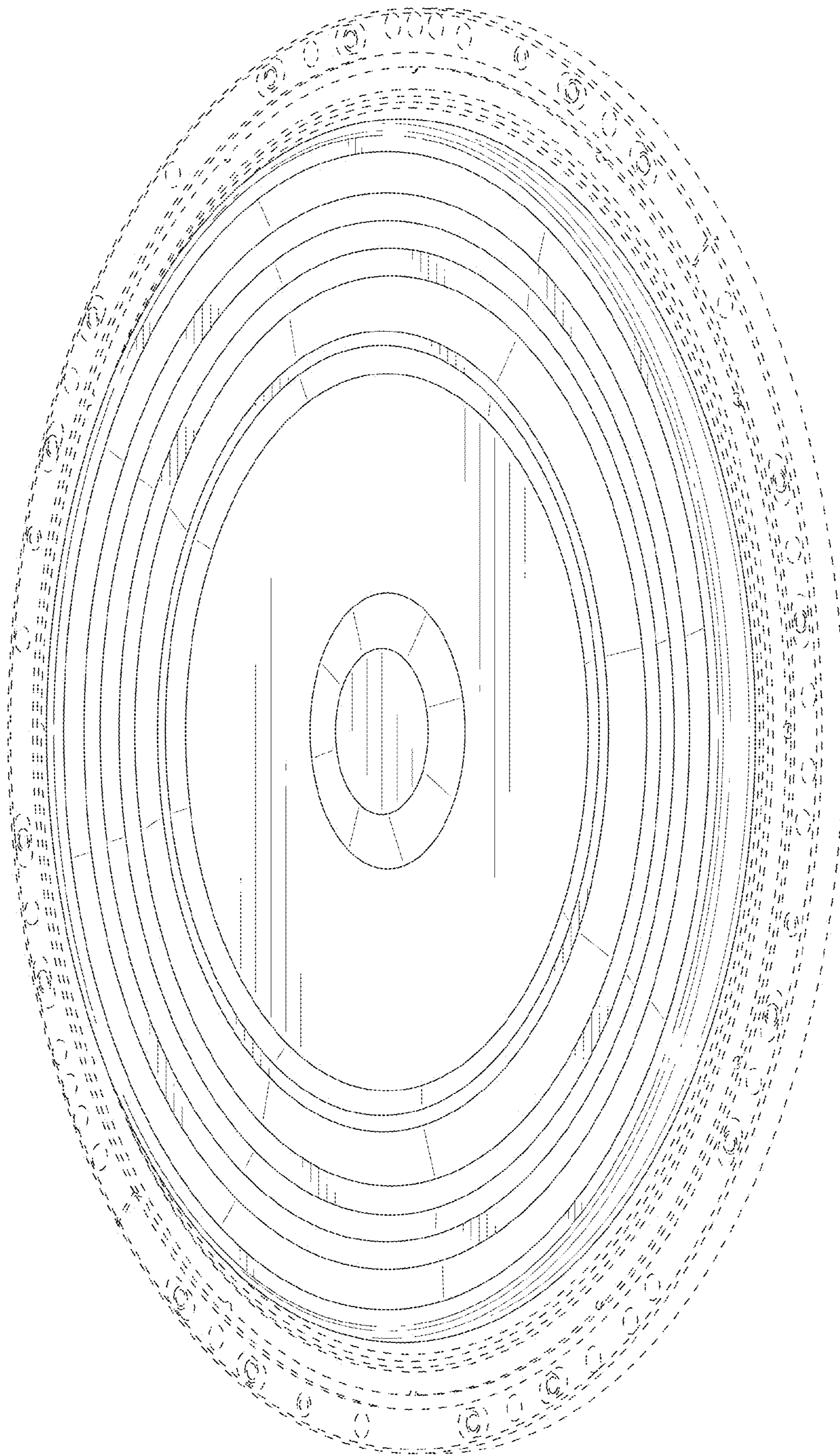


FIG. 1

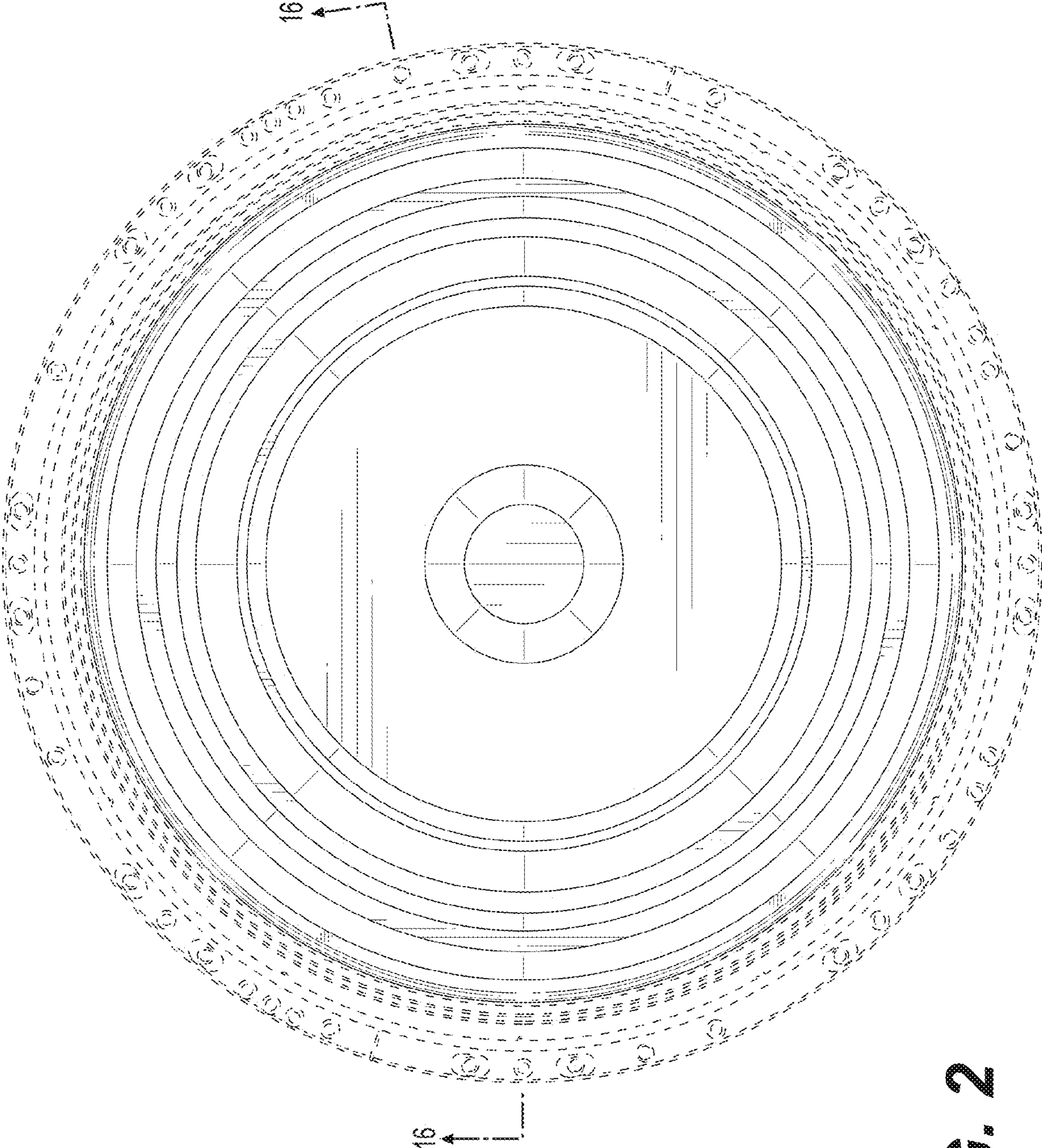


FIG. 2

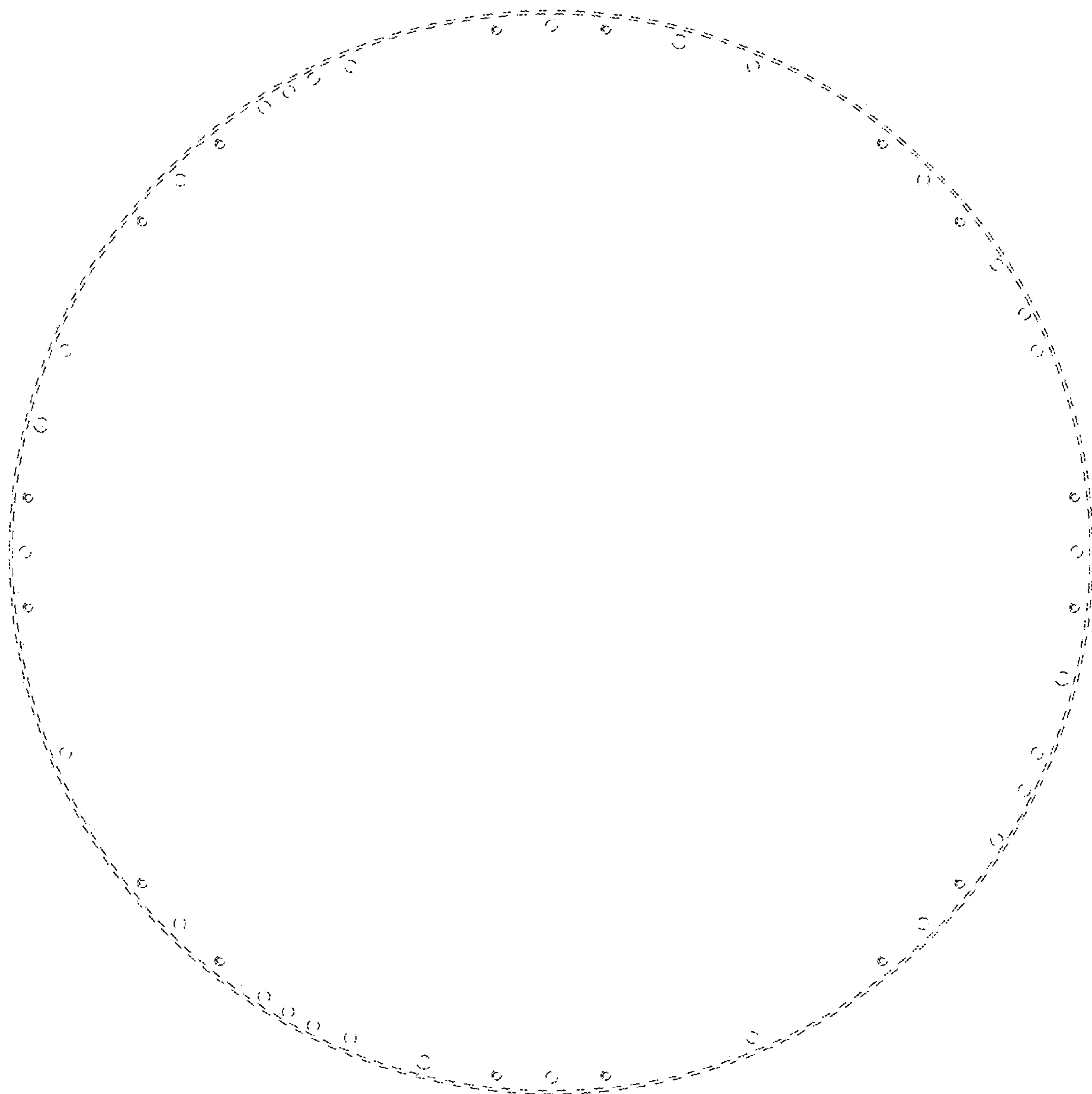


FIG. 3

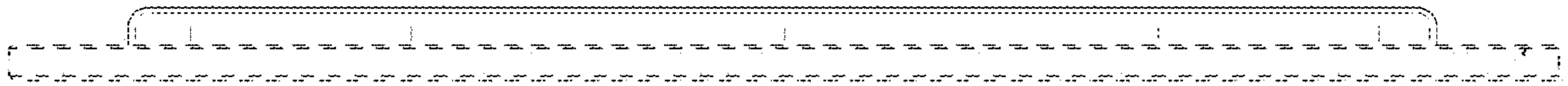


FIG. 4

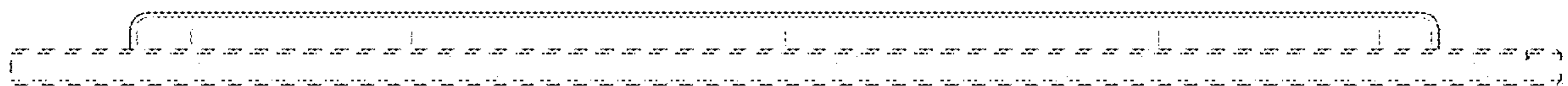


FIG. 5

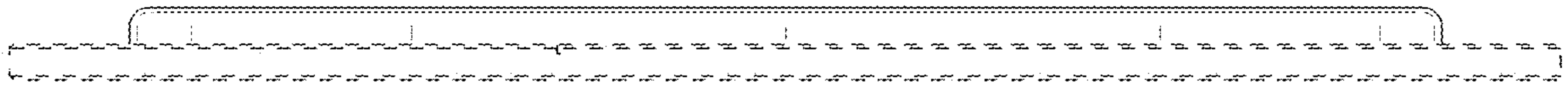


FIG. 6



FIG. 7

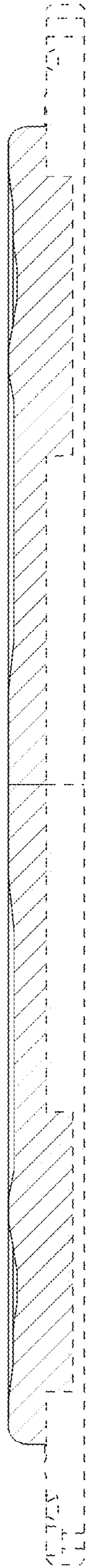


FIG. 8